

## Electronic Patent Application Fee Transmittal

<b>Application Number:</b>	10792038			
<b>Filing Date:</b>	03-Mar-2004			
<b>Title of Invention:</b>	Composition and process for post-etch removal of photoresist and/or sacrificial anti-reflective material deposited on a substrate			
<b>First Named Inventor/Applicant Name:</b>	Melissa K. Rath			
<b>Filer:</b>	Tristan Anne Fuierer			
<b>Attorney Docket Number:</b>	ATMI-668			
Filed as Large Entity				
<b>Utility under 35 USC 111(a) Filing Fees</b>				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
<b>Extension-of-Time:</b>				
Extension - 1 month with \$0 paid	1251	1	120	120

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Miscellaneous:</b>				
Request for continued examination	1801	1	810	810
<b>Total in USD (\$)</b>				<b>930</b>